

## Supplementary Materials

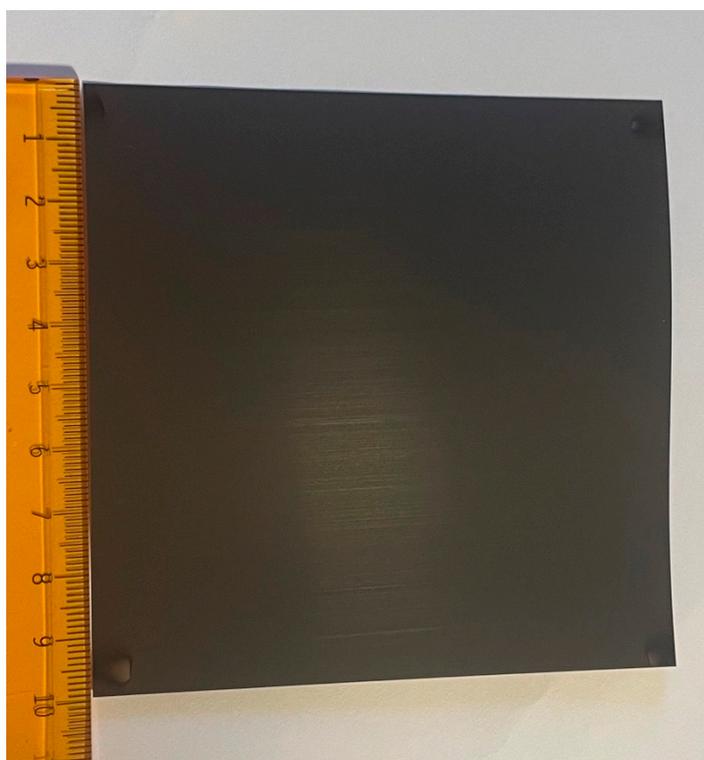
# Oxygen Defects Containing TiN Films for the Hydrogen Evolution Reaction: A Robust Thin-Film Electrocatalyst with Outstanding Performance

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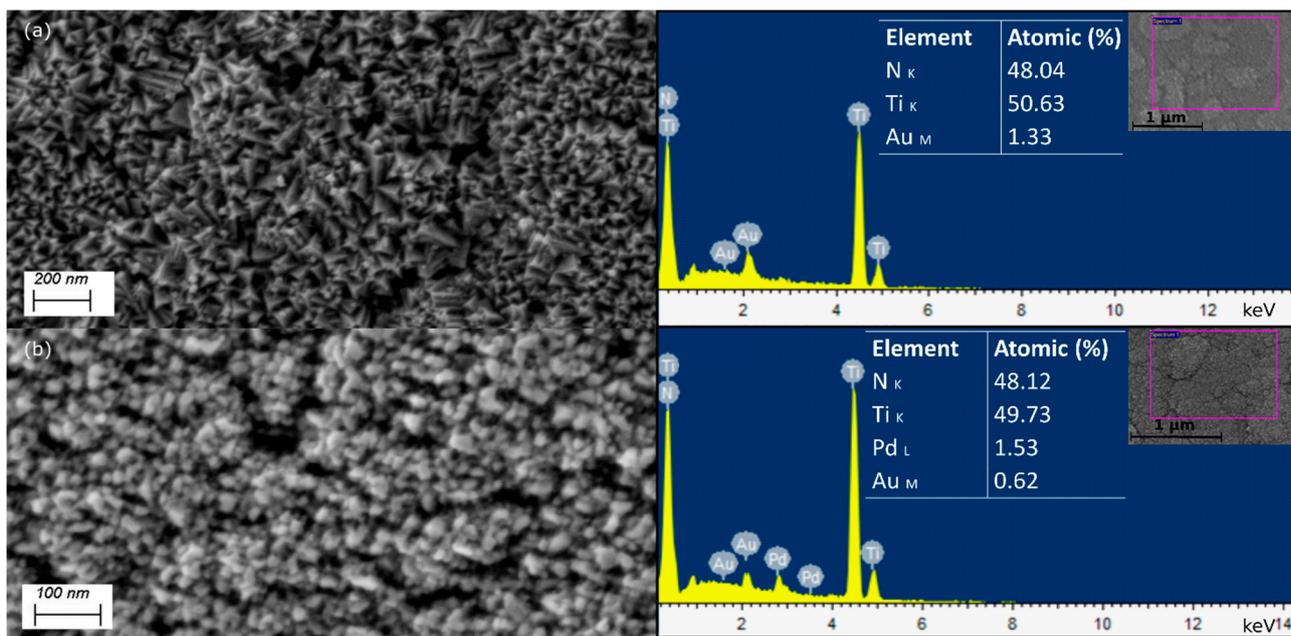
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**Figure S1:** a photograph of a large area TiNO film deposited on a Ti sheet.



**Figure S2:** Top view secondary electron (SE) micrographs of TiN (a) and TiN-PdNPs (b) together with their EDS analysis after HER studies.